



COPY OF PAPERS
ORIGINALLY FILED

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Zhimin Lu)	Group Art Unit Unknown
)	
Appl. No.	:	09/870,393)	I hereby certify that this correspondence and all
)	marked attachments are being deposited with
Filed	:	May 29, 2001)	the United States Postal Service as first-class
)	mail in an envelope addressed to: United States
For	:	METHOD AND APPARATUS)	Patent and Trademark Office, P.O. Box 2327,
		TO CORRECT WAFER DRIFT)	Arlington, VA 22202, on
)	
Examiner	:	Unknown)	<u>August 2, 2002</u>
)	(Date)
)	<u>Adeel S. Akhtar, Reg. No. 41,394</u>

PRELIMINARY AMENDMENT

United States Patent and Trademark Office
P.O. Box 2327
Arlington, VA 22202

Dear Sir:

Prior to examination on the merits, please amend the above-captioned application as follows:

IN THE SPECIFICATION:

Please amend the paragraph beginning on p. 16, line 3, as indicated in the replacement paragraph below:

The deviation in voltage readings are used to calculate 630 offsets Δ_L and Δ_R . Δ_L and Δ_R represent the linear deviations from the nominal wafer position, as measured longitudinally along the sensors (see Figure 12). Δ_L and Δ_R may be obtained from the following equation:

$$\Delta = \frac{l_{\max} - l_{\min}}{V_{\max} - V_{\min}} (V_{\text{ref}} - V)$$

Here, l_{\max} and l_{\min} represent maximum and minimum sensor laser beam lengths left unblocked by the wafer, V_{\max} and V_{\min} represent the output value of the sensors when l_{\max} and l_{\min} are left unblocked, V_{ref} indicates the sensor output value when the reference wafer is at the nominal